

IN THE CLAIMS:

1. (Currently Amended) A method of manufacturing an envelope which includes a first substrate, a second substrate opposed to the first substrate, and a space defining member which is located between the first substrate and the second substrate and has a substantially plate shape, the method comprising:

applying a tension to the space defining member;

fixing the space defining member to ~~which the tension is applied to~~ the first substrate at fixing points thereon separate from each other while applying a tension to the space defining member; and

releasing the tension from the space defining member fixed to the first substrate,

wherein in the fixing of the space defining member to the first substrate, ~~[[a]] the fixing point points~~ of the space defining member to the first substrate are ~~[[is]]~~ located between points at which the tension is exerted.

2. (Canceled)

3. (Canceled)

4. (Currently Amended) A method of manufacturing an electron beam apparatus which includes a first substrate having a plurality of electron-emitting devices on a surface thereof, a second substrate which is opposed to the first substrate and in which an

electrode that controls electrons emitted from the plurality of electron-emitting devices is formed, and at least one space defining member which is located between the first substrate and the second substrate and has a substantially plate shape, the method comprising:

applying a tension to the space defining member;

fixing the space defining member to ~~which the tension is applied to~~
the first substrate at fixing points thereon separate from each other while applying a tension to the space defining member; and

releasing the tension from the space defining member fixed to the first substrate,

wherein in the fixing of the ~~spacing space~~ defining member to the first substrate, ~~[[a]]~~ fixing ~~point~~ points of the space defining member to the first substrate ~~[[is]]~~ are located between points at which the tension is exerted.

5. (Canceled)

6. (Canceled)

7. (Previously Amended) A method of manufacturing an electron beam apparatus according to claim 4, wherein in the applying of the tension to the space defining member, the tension is applied by a spacer conveying unit.

8. (Previously Presented) A method of manufacturing an electron beam

apparatus according to claim 4, wherein in the applying of the tension to the space defining member, the tension is applied by a tension applying unit.

9. (Currently Amended) A method of manufacturing an electron beam apparatus according to claim 4, wherein the ~~interval specifying~~ space defining member has a base of an insulating property.

10. (Previously Presented) A method of manufacturing an electron beam apparatus according to claim 4, wherein the space defining member has a surface on which a high resistance film is formed.

11. (Previously Presented) A method of manufacturing an electron beam apparatus according to claim 10, wherein the high resistance film has a sheet resistance of 10^7 [Ω /square] or more and 10^{14} [Ω /square] or less.

12. (Currently Amended) A method of manufacturing an electron beam apparatus according to claim 4, wherein the first substrate further includes a plurality of wirings that electrically connect the plurality of electron-emitting devices and the ~~interval specifying members are~~ at least one space defining member is located on the wiring.